



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 8243**
Takeshi IWAI et al. : Docket No. 2001_1761A
Serial No. 09/993,627 : Group Art Unit 1752
Filed November 27, 2001 : Examiner John S.Y. Chu
POSITIVE-WORKING PHOTORESIST :
COMPOSITION

RESPONSE

RECEIVED
JAN 17 2004
TC 1700

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This is in response to the Official Action dated August 29, 2003, the period for response having being extended for one month by the attached petition.